

### TOTAL IONIZING DOSE TEST REPORT

No. 03T-RT54SX72S-T25KS008 September 17, 2003

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#### I. SUMMARY TABLE

Parameter	Tolerance
1. Gross Functionality	Passed 100 krad(Si)
2. I <sub>CC</sub>	Passed 75 krad(Si) for 25 mA spec, I <sub>CC</sub> averaging 65.5 mA after 100 krad(Si)
	and room temp annealing
3. Input Threshold (V <sub>TIL</sub> /V <sub>IH</sub> )	Passed 100 krad(Si)
4. Output Drives (V <sub>OL</sub> /V <sub>OH</sub> )	Passed 100 krad(Si)
5. Propagation Delays	Passed 100 krad(Si) for 10% degradation criterion
6. Transition Time	Passed 100 krad(Si)

### II. TOTAL IONIZING DOSE (TID) TESTING

# A. Device Under Test (DUT) and Irradiation

Table 1 lists the DUT information and irradiation conditions.

Table 1. DUT information and irradiation conditions

Part Number	RT54SX72S
Package	CQFP256
Foundry	Matsushita Electronics Corporation
Technology	0.25 μm CMOS
DUT Design	TDSX72CQFP256_2Strings
Die Lot Number	T25KS008
Quantity Tested	5
Serial Number	22245, 22253, 22255, 22272, 22275
Radiation Facility	Defense Microelectronics Activity
Radiation Source	Co-60
Dose Rate	1 krad(Si)/min (±5%)
Irradiation Temperature	Room
Irradiation and Measurement Bias	Static at 5.0 V/2.5 V
$(V_{CCI}/V_{CCA})$	

#### B. Test Method

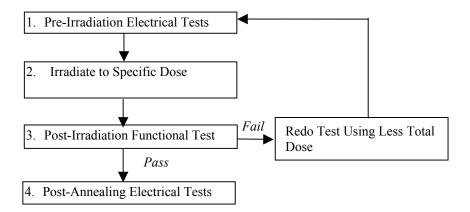


Fig 1 Parametric test flow chart

The parametric tests follow the military standard test method 1019.5. Fig 1 shows the testing flow. The time dependent effect (TDE) of this product was previously evaluated by comparing the results of a high dose rate (1 krad(Si)/min) against the results of a low dose rate (1 krad(Si)/hr). No adverse TDE was observed. Therefore the accelerated aging test (rebound test) is omitted. Room temperature annealing were performed for approximately one month after 100 krad(Si) of irradiation. DUTs were static biased during annealing.

#### C. Electrical Parameter Measurements

A high utilization design (TDSX72CQ256\_2Strings) to address total dose effects in typical space applications is used. The circuit schematics are shown in appendix A.

Table 2 lists the electrical parameters measured. The functionality is measured pre-irradiation, post-irradiation, and post-annealing on the output pin (O\_AND3 or O\_AND4) of the two combinational buffer-strings and on the output pins (O\_OR4 and O\_NAND4) of the shift register.  $I_{CC}$  is measured on the power supply of the logic-array ( $I_{CCA}$ ) and I/O ( $I_{CCI}$ ) respectively.

The input logic thresholds  $(V_{TIL}/V_{IH})$  and output drives  $(V_{OL}/V_{OH})$  are measured pre-irradiation and post-annealing on a combinational net, the input pin DA to the output pin QA0. The propagation delays are measured pre-irradiation and post-annealing on the O\_AND4 output of one of the buffer strings. The delay is defined as the time delay from the time of triggering edge at the CLOCK input to the time of switching state at the O\_AND4. The transient times (rise and fall times) are measured post-annealing on the O\_AND4.

Each unused input is grounded with an 1 M ohm resistor during irradiation and an 1.2K ohm resistor during annealing.

Table 2. Logic design for parametric tests

Parameter/Characteristics	Logic Design
1. Functionality	All key architectural functions (pins
	O_AND3, O_AND4, O_OR3, O_OR4, and
	O_NAND4)
2. $I_{CC} (I_{CCA}/I_{CCI})$	DUT power supply
3. Input Threshold (V <sub>TIL</sub> /V <sub>IH</sub> )	Input buffer (pin DA to QA0)
4. Output Drive (V <sub>OL</sub> /V <sub>OH</sub> )	Output buffer (pin DA to QA0)
5. Propagation Delay	String of buffers (pin LOADIN to O_AND4)
6. Transition Time	D flip-flop output (O_AND4)

#### III. TEST RESULTS

#### A. Functionality

Every DUT passed the gross functional test at pre-irradiation, post-irradiation, and post-annealing.

#### B. $I_{CC}$

Figs 2-6 show the in-flux  $I_{CC}$  plots. Table 3 lists the post-annealing  $I_{CC}$ .

Table 3. Post-annealing I<sub>CC</sub>

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DUT	I <sub>CCA</sub> (mA)	I <sub>CCI</sub> (mA)				
22245	49.5	17.7				
22253	33.4	4.9				
22255	68.3	9				
22272	55	18				
22275	65	6.9				

An empirical equation is used to extract the total dose tolerance after a 10 years annealing. The critical total dose ( $\gamma_{critical}$ ) for a 10-year mission to induce  $I_{CC}$  to 25 mA can be obtained by the equation:

$$I_{CCA}(\gamma_{critical}) \times 0.32 + I_{CCI}(\gamma_{critical}) \times 0.29 = 25mA$$

Where  $I_{CCA}(\gamma)$  and  $I_{CCI}(\gamma)$  are read from the raw data of the worst case, i.e. DUT 22272 (Fig 5). The tolerance  $(\gamma_{critical})$  is obtained as approximately 75 krad(Si). This extracted tolerance is very conservative. Experiments have shown that a DUT irradiated at high dose rate and then annealed for the duration to match the total mission time results a significantly higher  $I_{CC}$  than that of a DUT, manufactured by the same technology, irradiated at a low, uniform dose rate throughout the total mission time.



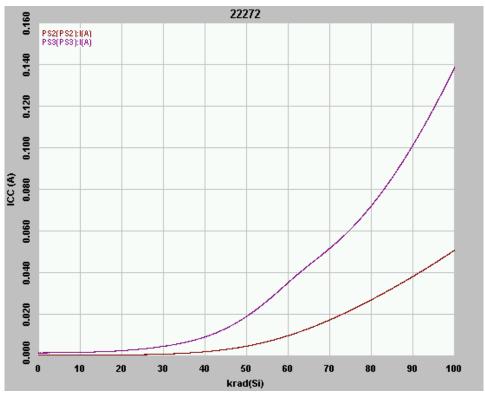
In-flux  $I_{CC}$  of DUT 22245, PS2 supplies  $I_{CCI}$  and PS3 supplies  $I_{CCA}$ . Fig 2



Fig 3



Fig 4



In-flux  $I_{CC}$  of DUT 22272, PS2 supplies  $I_{CCI}$  and PS3 supplies  $I_{CCA}$ . Fig 5

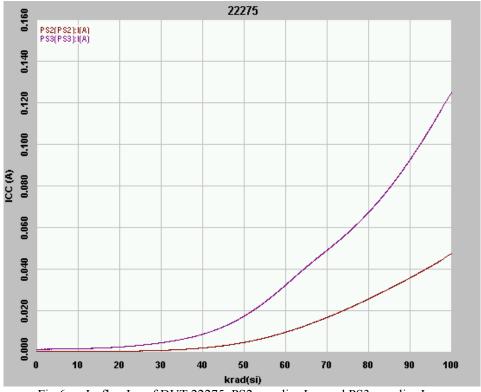


Fig 6 In-flux  $I_{CC}$  of DUT 22275, PS2 supplies  $I_{CCI}$  and PS3 supplies  $I_{CCA}$ .

### C. Input Logic Threshold $(V_{IL}/V_{IH})$

Table 4 lists the pre-irradiation and post-annealing input logic threshold. All data are within the spec limits.

Table 4 Pre-irradiation and post-annealing input logic threshold in volts

DUT	Pre-Irradia	ation	Post-Annealing		
DOT	$V_{\rm IL}$	$V_{IH}$	$V_{\mathrm{IL}}$	$V_{ m IH}$	
22245	1.25	1.48	1.32	1.42	
22253	1.38	1.43	1.33	1.42	
22255	1.41	1.45	1.32	1.42	
22272	1.40	1.45	1.31	1.41	
22275	1.41	1.45	1.32	1.41	

### D. Output Characteristics ( $V_{OL}/V_{OH}$ )

The pre-irradiation and post-annealing  $V_{\text{OI}}/V_{\text{OH}}$  are listed in table 5 and 6. The post-annealing data are within the spec limits, and 100 krad(Si) radiation has little effect on these parameters.

Table 5 Pre-irradiation and post-annealing V<sub>OL</sub> (in volts) at various sinking current

Tuote 5 The intudation and post annearing Vol. (in voite) at various sinking earlier										
DUT	1 mA		12 mA		20	mA	50 r	nA	100	mA
DUI	Pre-rad	Pos-an								
22245	0.009	0.010	0.100	0.110	0.170	0.180	0.430	0.430	0.880	0.890
22253	0.010	0.010	0.120	0.120	0.200	0.200	0.490	0.490	1.000	1.000
22255	0.009	0.020	0.100	0.110	0.170	0.180	0.430	0.430	0.880	0.880
22272	0.009	0.010	0.100	0.110	0.170	0.180	0.430	0.430	0.880	0.890
22275	0.009	0.010	0.100	0.110	0.170	0.170	0.430	0.430	0.880	0.880

Table 6 Pre-irradiation and post-annealing  $V_{\text{OH}}$  (in volts) at various sourcing current

	Tuote of the intudation and post aimeaning von (in voits) at various sourcing earlier									
DUT	1 mA		8 mA		20	mA	50 r	nA	100	mA
DOI	Pre-rad	Pos-an	Pre-rad	Pos-an	Pre-rad	Pos-an	Pre-rad	Pos-an	Pre-rad	Pos-an
22245	4.990	4.980	4.870	4.860	4.670	4.660	4.130	4.120	3.050	3.020
22253	4.990	4.980	4.860	4.860	4.640	4.640	4.060	4.050	2.910	2.890
22255	4.990	4.980	4.870	4.860	4.660	4.650	4.120	4.100	3.020	2.970
22272	4.990	4.980	4.870	4.860	4.660	4.660	4.120	4.100	3.020	2.980
22275	4.990	4.980	4.870	4.860	4.660	4.650	4.120	4.100	3.020	2.960

## E. Propagation Delays

Tables 7 and 8 list the pre-irradiation and post-annealing propagation delays, and radiation-induced degradations. The radiation-induced degradations are less than 5%.

Table 7 Low to high delays (in nanoseconds)

DUT	Pre-Irradiation	Post-Anneal	Degradation (%)
22245	1233.6	1287.4	4.36
22253	1238.8	1243.5	0.38
22255	1235.9	1262.4	2.14
22272	1245.9	1300.5	4.38
22275	1236.6	1266.7	2.43

Table 8 High to low delays (in nanoseconds)

DUT	Pre-Irradiation	Post-Anneal	Degradation (%)
22245	1085.9	1133.1	4.35
22253	1077.0	1083.7	0.62
22255	1091.6	1114.0	2.05
22272	1080.8	1125.4	4.13
22275	1093.7	1116.1	2.05

## F. Transition Time

The post-annealing rising and falling edges are plotted in Figs 8-12. In every case, the transition time is approximately 2 nanoseconds.

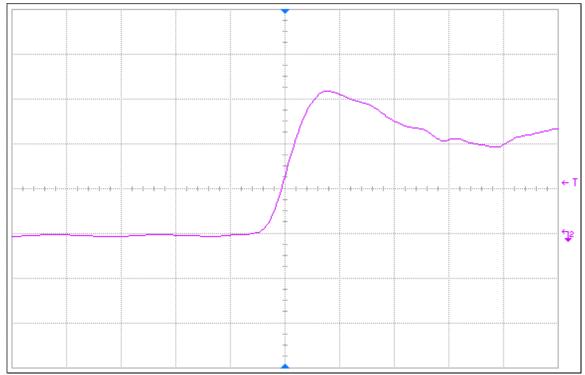


Fig 8(a) Post-annealing rising edge of DUT 22245, abscissa scale is 2 V/div and ordinate scale is 2 ns/div.

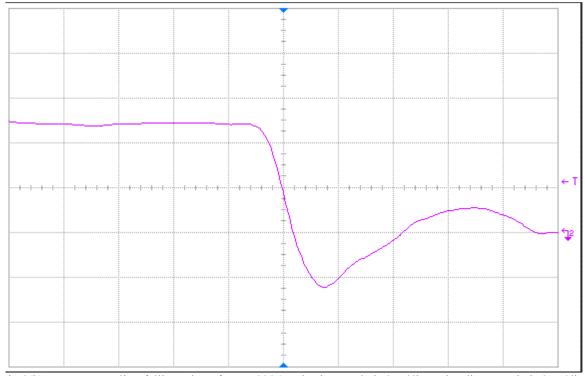


Fig 8(b) Post-annealing falling edge of DUT 22245, abscissa scale is 2 V/div and ordinate scale is 2 ns/div.

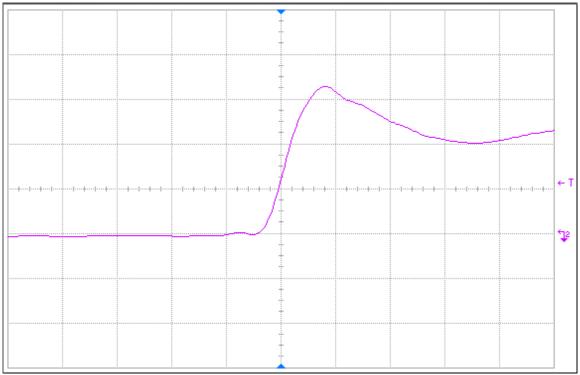


Fig 9(a) Post-annealing rising edge of DUT 22253, abscissa scale is 2 V/div and ordinate scale is 2 ns/div.

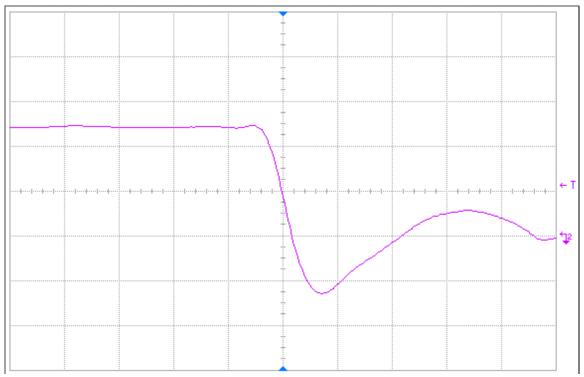


Fig 9(b) Post-annealing falling edge of DUT 22253, abscissa scale is 2 V/div and ordinate scale is 2 ns/div.

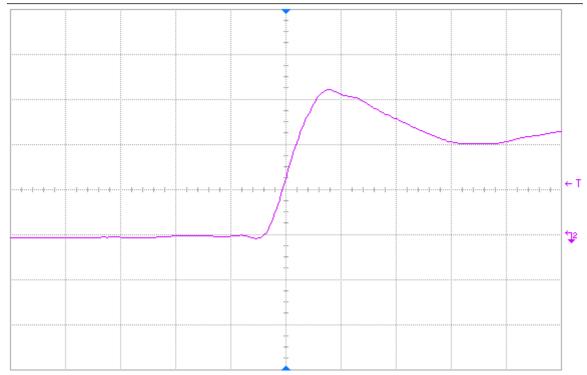


Fig 10(a) Post-annealing rising edge of DUT 22255, abscissa scale is 2 V/div and ordinate scale is 2 ns/div.

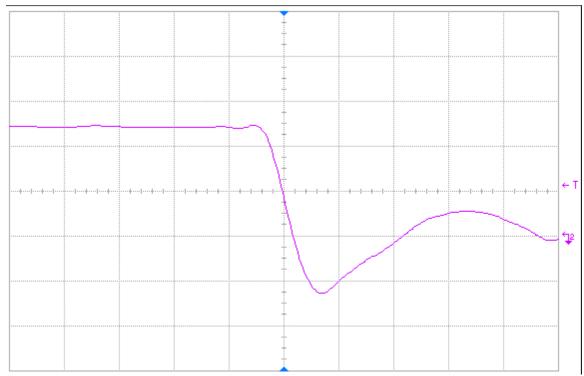


Fig 10(b) Post-annealing falling edge of DUT 22255, abscissa scale is 2 V/div and ordinate scale is 2 ns/div.

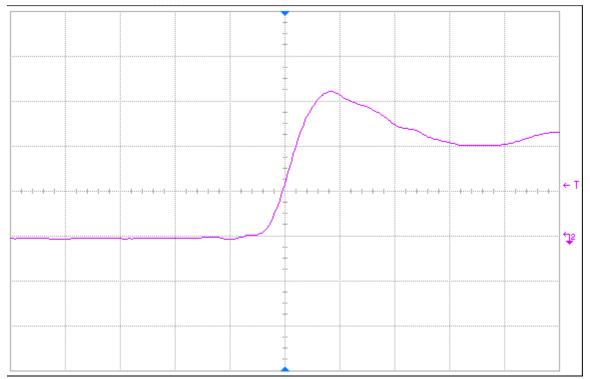


Fig 11(a) Post-annealing rising edge of DUT 22272, abscissa scale is 2 V/div and ordinate scale is 2 ns/div.

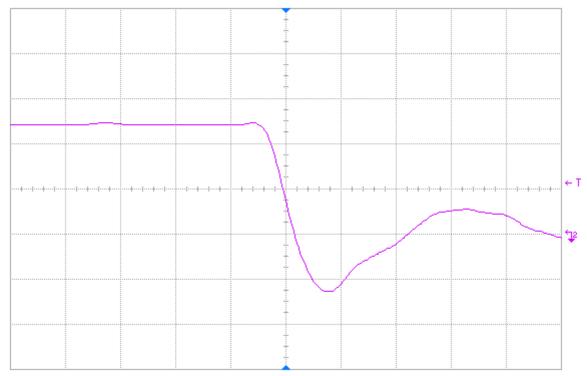


Fig 11(b) Post-annealing falling edge of DUT 22272, abscissa scale is 2 V/div and ordinate scale is 2 ns/div.

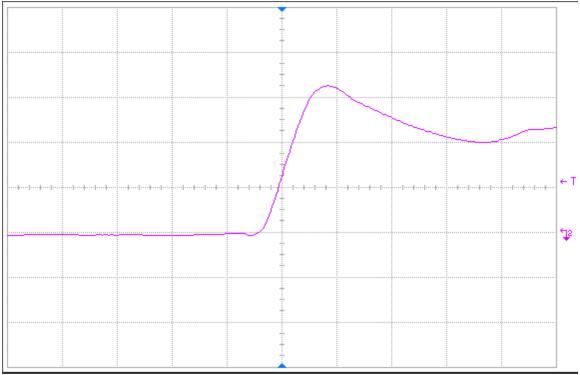


Fig 12(a) Post-annealing rising edge of DUT 22275, abscissa scale is 2 V/div and ordinate scale is 2 ns/div.

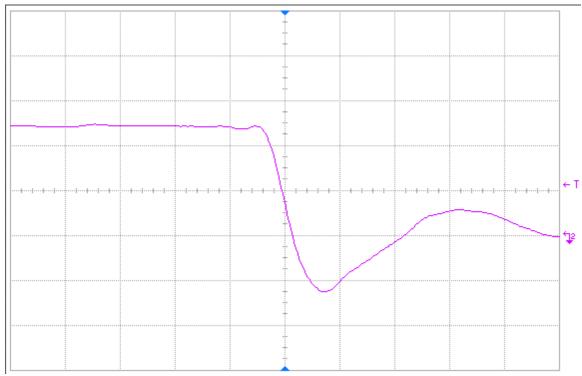


Fig 12(b) Post-annealing falling edge of DUT 22275, abscissa scale is 2 V/div and ordinate scale is 2 ns/div.

# APPENDIX A DUT DESIGN SCHEMATICS

